

PATENT

Serial No. 10/822,326

Docket No. JSF01-0041/WJT08-0068

1. (Original) A method of fabricating a tunable dielectric slurry, comprising:
depositing a thick film tunable dielectric onto a substrate;
subjecting said thick film to Ultra Violet (UV) radiation exposure after it is coated onto said substrate;
drying and baking said thick film and said substrate;
applying a developer to said thick film and said substrate, said developer capable of washing away an unexposed area of said thick film and retaining an exposed area enabling a latent pattern to be brought out and thus creating a patterned film; and
sintering said substrate.
2. (Original) The method of claim 1, wherein said thick film is screen printed onto said substrate.
3. (Original) The method of claim 2, wherein said thick film is thixotropic.
4. (Original) The method of claim 1, wherein said thick film is spin coated onto said substrate.
5. (Original) The method of claim 4, wherein said thick film is Newtonian.
6. (Original) The method of claim 1, wherein said step of depositing a thick film onto a substrate is accomplished by a technique selected from a group consisting of:
transfer coating;